

# Fabrications and Characteristics of Low-noise La-Ca-Sr-Mn-O Thin-film Thermometers

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## ABSTRACT

La<sub>0.75</sub>Ca<sub>0.15</sub>Sr<sub>0.1</sub>MnO<sub>3</sub> (LCSMO) thin films were grown on NdGaO<sub>3</sub>(110) substrates by using RF magnetron sputtering. Here the samples were deposited at different growth temperatures to probe the effect of growth temperature on this film properties. We used the standard 4-probe measurement to obtain the resistance-temperature curves. The crystalline structure and the strains in films were characterized by the X-ray diffractometer. The optimum performance is found in LCSMO grown at 610 °C with low strain, which show a temperature coefficient of resistance (TCR) ~ 4.9 %K-1 at 301 K and a noise equivalent temperature (NET) of 8 × 10<sup>-7</sup> KHz<sup>-0.5</sup> at 300 K with f = 30 Hz and I = 0.3 mA. This obtained NET value is much lower than those of other uncooled thermometers such as semiconducting YBa<sub>2</sub>Cu<sub>3</sub>O<sub>6</sub>, or vanadium oxides. We demonstrate that the LCSMO films have real potential for the application on uncooled bolometric devices.

Keywords : infrared detector、temperature coefficient of resistance、colossal magnetoresistance material

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## REFERENCES

- [1] 賴耿陽, 紅外線工學基礎應用. 臺灣復文興業[2] Joo-Hyung Kim, KTH Information and Communication Technology, Doctoral Thesis, Stockholm 2005.
- [3] K. Chahara, T. Ohno, M. Kasai, and Y. Kozono, *Appl. Phys. Lett.* 63, 1990 (1993).
- [4] R. von Helmlot, J. Weckerg, B. Holzapfel, L. Schultz, and K. Samwer, *Phys. Rev. Lett.* 71, 2331 (1993).
- [5] S. Jin, T. H. Tiefel, M. McCormack, R. A. Fastnacht, R. Ramesh, and L. H. Chen, *Science* 264, 413 (1994).
- [6] Fan Yang, Laurence M?chin, Jean-Marc Routoure, and Bruno Guillet, *Journal of Applied Physics* 99, 024903 (2006).
- [7] Alvydas Lisauskas, S. I. Khartsev, and Alex Grishina, *Appl. Phys. Lett.* 77, 756 (2000).
- [8] A. Goyal, M. Rajeswari, R. Shreekala, S. E. Lofland, S. M. Bhagat, T. Boettcher, C. Kwon, R. Ramesh, and T. Venkatesan, *Appl. Phys. Lett.* 71, 27 (1997).
- [9] CHEN Xi-Qu, YI Xin-Jian, and WANG Qiang, *J. Infrared Millim. Waves* 25, 246 (2006).
- [10] R. Mahendiran, R. Mahesh, A.K. Raychaudhuri, and C.N.R. Rao, *Solid State Communications* 94, 515 (1995).
- [11] A. Urushibara, Y. Moritomo, T. Arima, A. Asamitsu, G. Kido, and Y. Tokura, *Phys. Rev. B* 51, 14105 (1995).
- [12] 吳智淵, 大葉大學, 95年碩士論文[13] B. Vengalis, A. Maneikis, F. Anisimovas, R. Butkute5, L. Dapkus, and A. Kindurys, *Journal of Magnetism and Magnetic Materials* 211, 35 (2000).
- [14] J. B. Johnson, *Phys. Rev.* 32, 97 (1928).
- [15] 張慶瑞, 常磁電阻與異向磁電阻, 中華民國磁性技術協會會訊第十九期, 5 (1999).
- [16] Clarence Zener, *Phys. Rev.* 82, 403 (1951).
- [17] Y. P. Lee, S. Y. Park, J. S. Park, V. G. Prokhorov, V. A. Komashko, V. L. Svetchnikov, and J.-H. Kang, *Journal of Applied Physics* 101, 053708 (2007).
- [18] Xiong C. S., Cui Y. F., Xiong Y. H., Pi H. L., Bao X. C., Huang Q. P., Zeng Y., Wei F. F., Zheng C. F., and Zhu J, *Journal of Solid State Chemistry* 181, 2123 (2008).
- [19] Laurence M?chin, Jean-Marc Routoure, Bruno Guillet, Fan Yang, St?phane Flament, and Didier Robbes, *Appl. Phys. Lett.* 87, 204103 (2005).

- [20] Laurence M?chin, Jean-Marc Routoure, Silvana Mercone, Fan Yang, St?phane Flament, and Radoslav A. Chakalov, Journal of Applied Physics 103, 083709 (2008).
- [21] 許仲男, 大葉大學, 94年碩士論文[22] 洪連輝, 固態物理學導論, 高立圖書[23] 許樹恩, 吳泰伯, X光繞射原理與材料結構分析, 中國材料科學學會[24] 張煦, 李學養, 磁性物理學, 聯經出版社[25] Serway, and Jewett, Principles of Physics 3rd ed.
- [26] Adel S. Sedra, and Kenneth C. Smith, Microelectronic Circuits.
- [27] 陳志堯, 中央大學, 89年碩士論文[28] 許智鈞, 中山大學, 89年碩士論文[29] 許信國, 中山大學, 95年大學論文[30] 簡百鴻, 中央大學, 95年大學論文[31] J.-H. Kim, S. I. Khartsev, and A. M. Grishina, Appl. Phys. Lett. 82, 4295 (2003).
- [32] M. Rajeswari, C. H. Chen, A. Goyal, C. Kwon, M. C. Robson, R. Ramesh, and T. Venkatesan, Appl. Phys. Lett. 68, 3555 (1996).
- [33] P. Martyniuk, and A. Rogalski, Progress in Quantum Electronics 32, 89 (2008).
- [34] J.L. Tissot, Infrared Physics & Technology 46, 147 (2004).
- [35] Sherif Sedky, Paolo Fiorini, Kris Baert, Lou Hermans, and Robert Mertens, IEEE Transactions on Electron Devices 46, 675 (1999).
- [36] Mahmoud Almasri, Zeynep ?elik-Butler, Donald P. Butler, Alparslan Yaradanakul, and Ali Yildiz, Journal of Microelectromechanical System 11, 528 (2002).
- [37] Young Sun, and M. B. Salamon, Journal of Applied Physics 92, 3235 (2002).
- [38] B. Raquet, J. M. D. Coey, S. Wirth, and S. von Molna?r, Phys. Rev. B. 59, 12435 (1999).
- [39] Young-Min Kang, Alexander N. Ulyanov, Geo-Myung Shin, Sung-Yun Lee, Dae-Gil Yoo, and Sang-Im Yooa, Journal of Applied Physics 105, 07D711 (2009).
- [40] R. J. Choudhary, Anjali S. Ogale, S. R. Shinde, S. Hullavarad, S. B. Ogale, and T. Venkatesan, Appl. Phys. Lett. 84, 3846 (2004).
- [41] 蔣慶有, 大葉大學, 96年碩士論文